

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	("6508920").PN.	US-PGPUB; USPAT	OR	OFF	2008/06/06 08:22
L2	76993	electroplat\$ or electro-plat\$ or electrodeposit\$ or electro-deposit\$	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:23
L3	17987	(electrolyt\$ or electro-lyt\$ or electrochem\$ or electro-chem\$) near2 (deposit\$)	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:23
L4	21350	(electrolyt\$ or electro-lyt\$ or electrochem\$ or electro-chem\$) near2 (plate or plates or plated or plating)	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:23
L5	99600	l2 or l3 or l4	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:24
L6	800950	semiconductor or wafer	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:24
L7	193436	seed	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:24
L8	392697	barrier	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:24
L9	201297	anneal or anneals or annealed or annealing	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:25
L10	41477	temperature adj gradient	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:25
L11	938	l9 same l10	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:25
L12	24	l11 and l8 and l7 and l6 and l5	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:26

L13	7	(09/386734   09/733608   09/882613   09/885451   10/189678   10/801460   11/056704   11/199570   11/199572   11/199592   11/199593   11/438424   11/682406).APP.	USPAT; USOCR	ADJ	ON	2008/06/06 09:26
L14	17	I12 not I13	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:26
L15	85	"RITZDORF THOMAS L\$".in.	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:34
L16	4286	(temperature adj gradient).clm.	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:35
L17	4	I15 and I16	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:35
L18	25	"STEVENS ES HENRY".in.	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:37
L19	5	I18 and I16	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:38
L20	1	I19 not I17	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:38
L21	72	"CHEN LINLIN".in.	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:39
L22	5	I21 and I16	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:39
L23	0	I22 not (I17 or I20)	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:40
L24	50	"GRAHAM LYNDON W\$".in.	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:40
L25	5	I24 and I16	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:40
L26	0	I25 not (I17 or I20)	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:40
L27	25	"DUNDAS CURT".in.	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:41
L28	5	I27 and I16	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:41
L29	0	I28 not (I17 or I20)	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:41

L30	55874	electroplat\$ or electro-plat\$ or electrodeposit\$ or electro-deposit\$	EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/06 09:47
L31	6265	(electrolyt\$ or electro-lyt\$ or electrochem\$ or electro-chem\$) near2 (deposit\$)	EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/06 09:48
L32	15813	(electrolyt\$ or electro-lyt\$ or electrochem\$ or electro-chem\$) near2 (plate or plates or plated or plating)	EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/06 09:48
L33	74976	I30 or I31 or I32	EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/06 09:48
L34	1343811	semiconductor or wafer	EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/06 09:48
L35	109981	seed	EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/06 09:48
L36	182014	barrier	EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/06 09:48
L37	95595	anneal or anneals or annealed or annealing	EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/06 09:49
L38	14780	temperature adj gradient	EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/06 09:49
L39	0	I33 and I34 and I35 and I36 and I37 and I38	EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/06 09:49
L40	0	I33 and I34 and I37 and I38	EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/06/06 09:49

6/6/08 9:51:14 AM